

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	8365	scanning and exposure and (mask reticle) and wafer	USPAT; US-PGPUB
2	BRS	L2	2989	1 and photolithography	USPAT; US-PGPUB
3	BRS	L3	594	2 and @ad<19960930	USPAT; US-PGPUB
4	BRS	L4	458	3 and optical	USPAT; US-PGPUB
5	BRS	L5	71	4 and titanium	USPAT; US-PGPUB
6	BRS	L6	15	5 and mirror	USPAT; US-PGPUB